



Docket No.: 543822004700
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Siegfried SCHWARZL et al.

Application No.: 10/812,411

Confirmation No.: 1274

Filed: March 30, 2004

Art Unit: 1763

For: EUV LITHOGRAPHY SYSTEM AND CHUCK
FOR RELEASING RETICLE IN A VACUUM
ISOLATED ENVIRONMENT

Examiner: K. A. Moore

AMENDMENT AFTER FINAL ACTION UNDER 37 C.F.R. 1.116

MS AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INTRODUCTORY COMMENTS

In response to the final Office Action dated November 22, 2006, please amend this application as follows.

Amendments to the Claims are reflected in the listing of claims which begins on page

2.

Remarks/Arguments begin on page 6 of this paper.

DO NOT ENTER 3/15/07 YW